



# COMSOL Multi-Physics Applied to MEMS Simulation and Design

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- 3. Thermal behavior of acoustic wave microbolometer*
- 4. Fluid-structure interaction (FSI) model for piezoelectric based energy harvest*

# **AIN based LAMB WAVE pressure sensor**

# AlN based LAMB WAVE pressure sensor

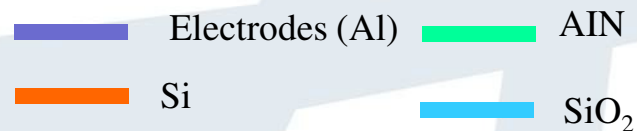
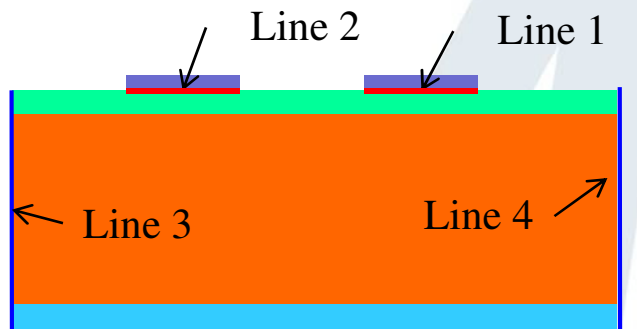
The simulation is to investigate the nature characteristics of a novel ruggedized high temperature **pressure sensor** operating in **lateral field exited (LFE) Lamb wave mode**, which can be operated in harsh environment such as oil & gas exploration, automobile and aeronautic applications.

The **comb-like structure electrodes** on top of aluminum nitride (AlN) were used to generate the wave. A Membrane was fabricated on SOI wafer with **10  $\mu\text{m}$ , 30  $\mu\text{m}$  and 50  $\mu\text{m}$  thick silicon** device layer.

The **phase velocity dispersive curve** of the Lamb wave under different Si thickness (Bulk, 10  $\mu\text{m}$ , 30  $\mu\text{m}$  and 50  $\mu\text{m}$ ) are simulated. Compared with the phase velocity dispersion curves of Lamb wave in pure AlN/Al plate that has been reported before, **higher order Lamb wave mode are observed** with a **non-dispersive behavior** over a wide range (from 10 to 50  $\mu\text{m}$  Si thickness) comparable to  $S_0$  mode for thin plates.

# Simulation approach

Physics employed: Piezoelectric Devices (pzd)



*Condition setting:*

Piezoelectric material model 1	AlN	Periodic Condition 1	Line 3,4
Free 1	default	Zero charge 1	default
Initial values 1	default	Electrical material model 1	Al, Si, SiO <sub>2</sub>
Ground 1	Line 1	Global Definitions: Parameters	Lambda: 20 μm
Electric potential 1	Line 2, V <sub>0</sub> =1 V		
Linear Elastic Material Model 1	Al, Si, SiO <sub>2</sub>		

**Mesh setting:**

Sequence type: Physics-controlled mesh

Element size: Normal

**Study 1:**

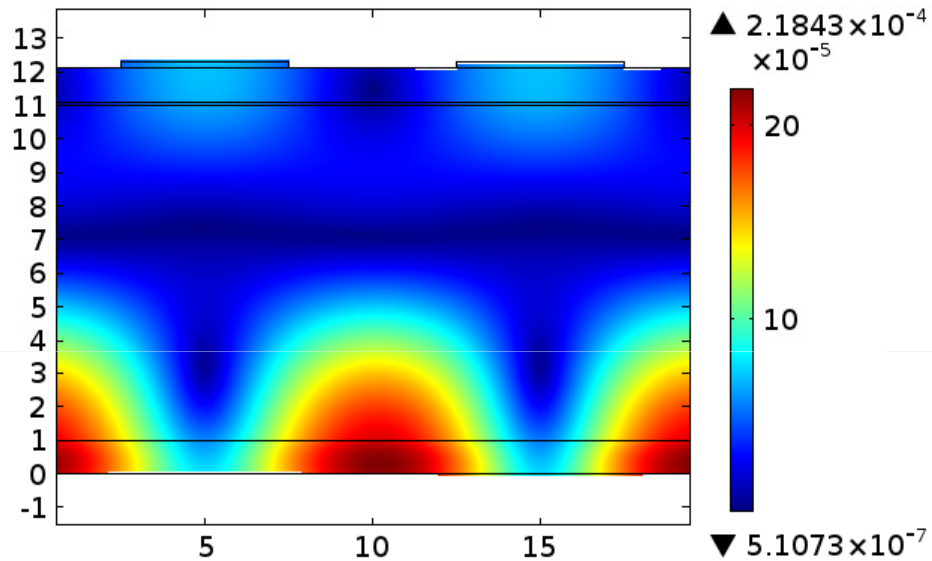
Step: Frequency Domain

Frequency: 200 MHz-1000 MHz

*Simulation: different thickness of AlN to lambda ratio (0.05-0.4) vs phase velocity have been investigated on different structures with underneath Si layer of thickness 10 μm, 30 μm, 50 μm, bulk Si and pure AlN*

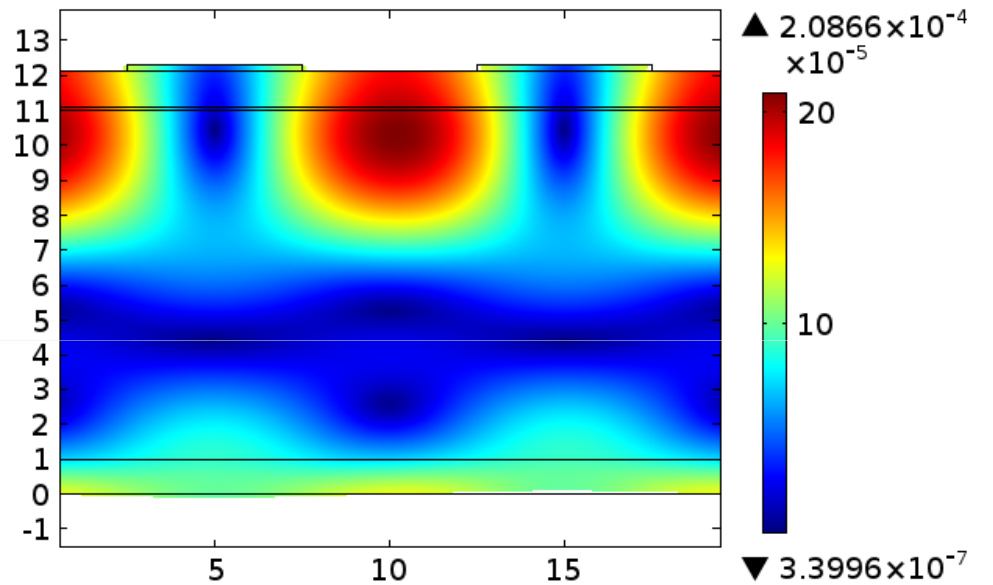
# Simulation results

Si thickness of 10  $\mu\text{m}$ :



442.12 MHz

$S_0$  wave

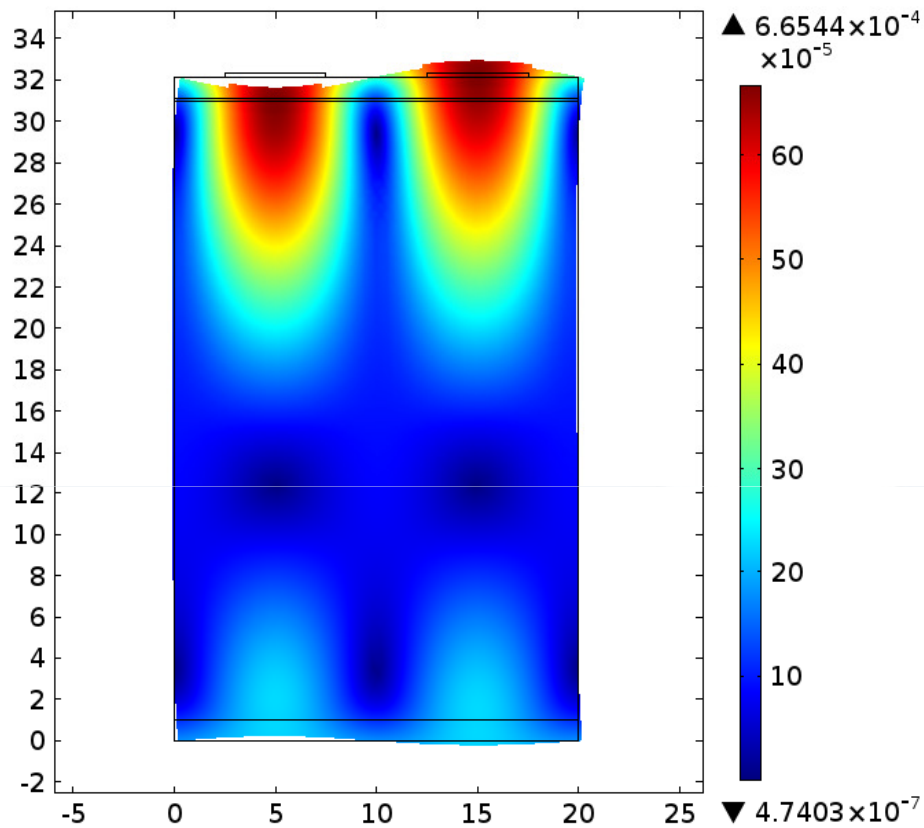


502.98 MHz

Lamb wave

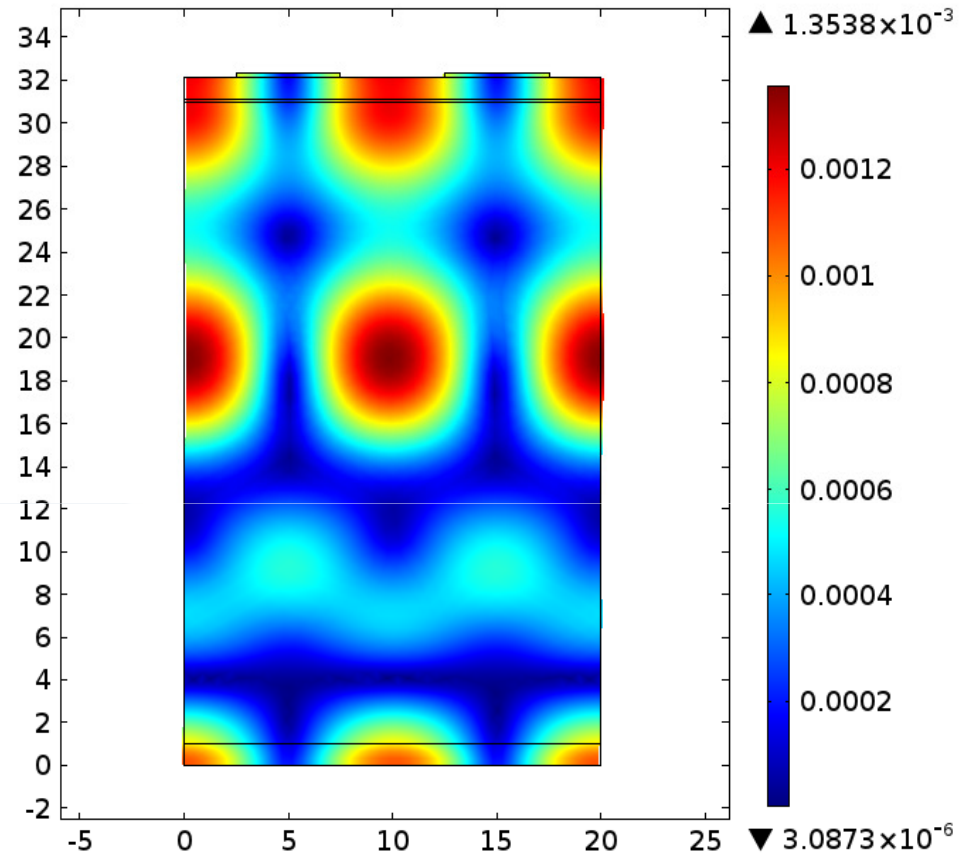
# Simulation results

Si thickness of 30  $\mu\text{m}$ :



**247.80 MHz**

$S_0$  wave

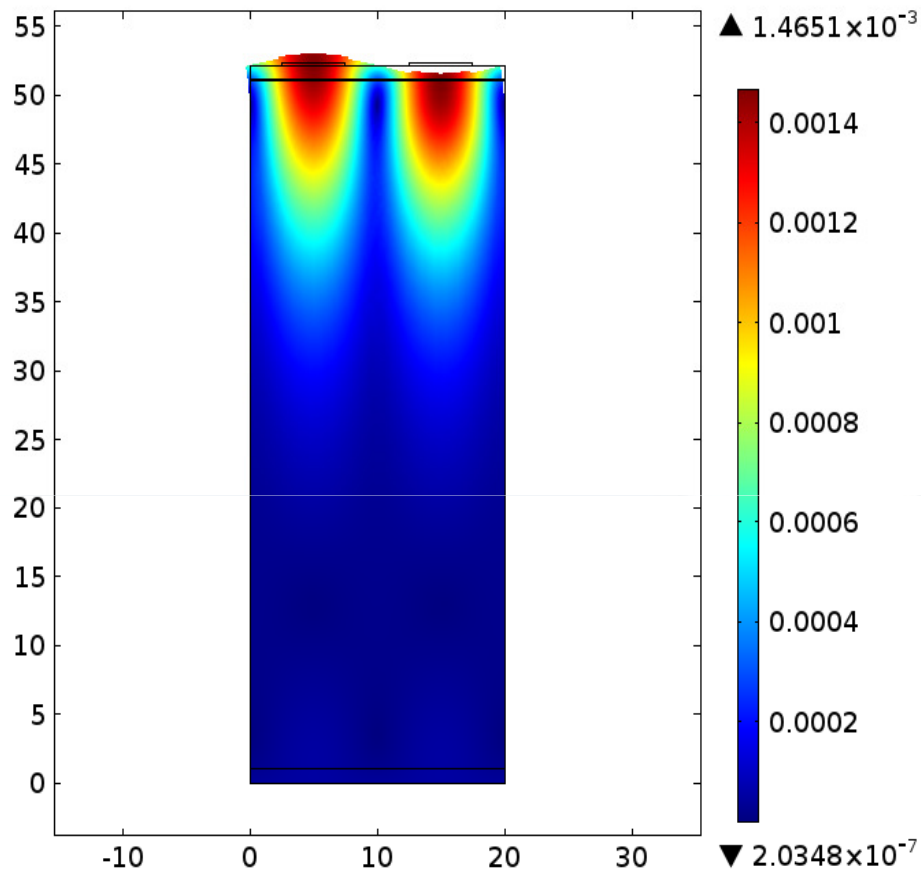


**503.15 MHz**

Lamb wave

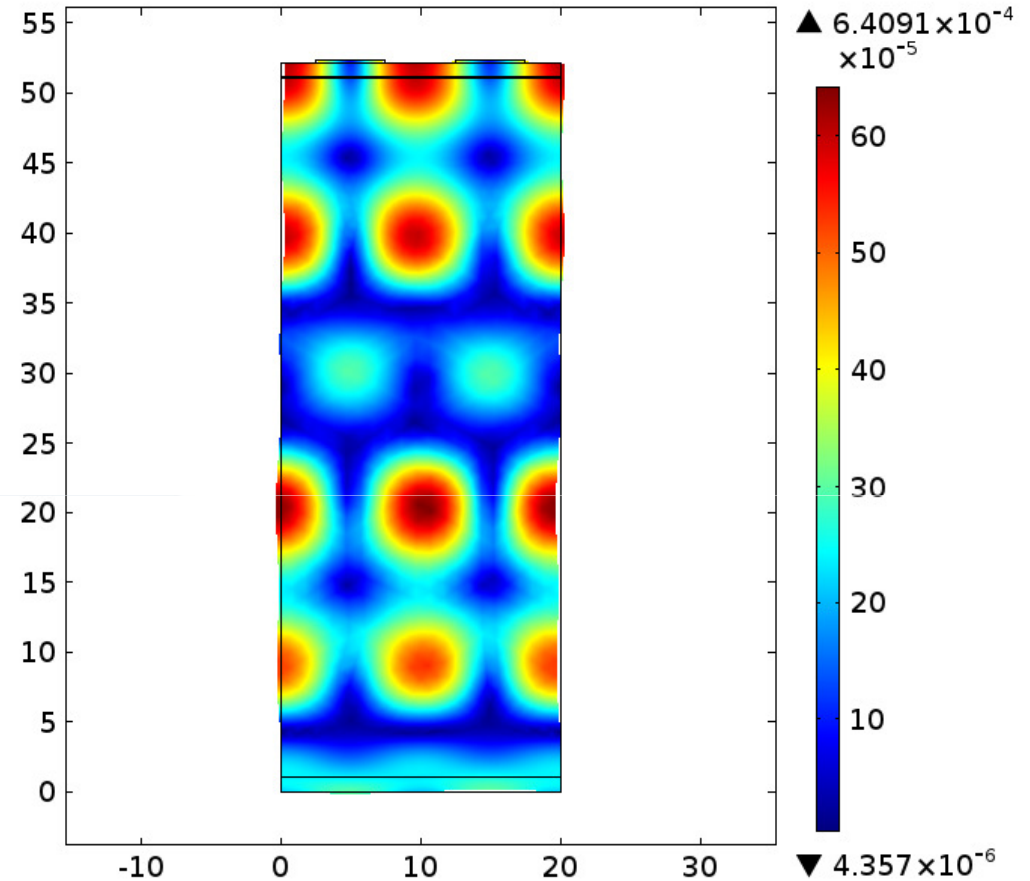
# Simulation results

Si thickness of 50  $\mu\text{m}$ :



**246.41MHz**

$S_0$  wave /SAW

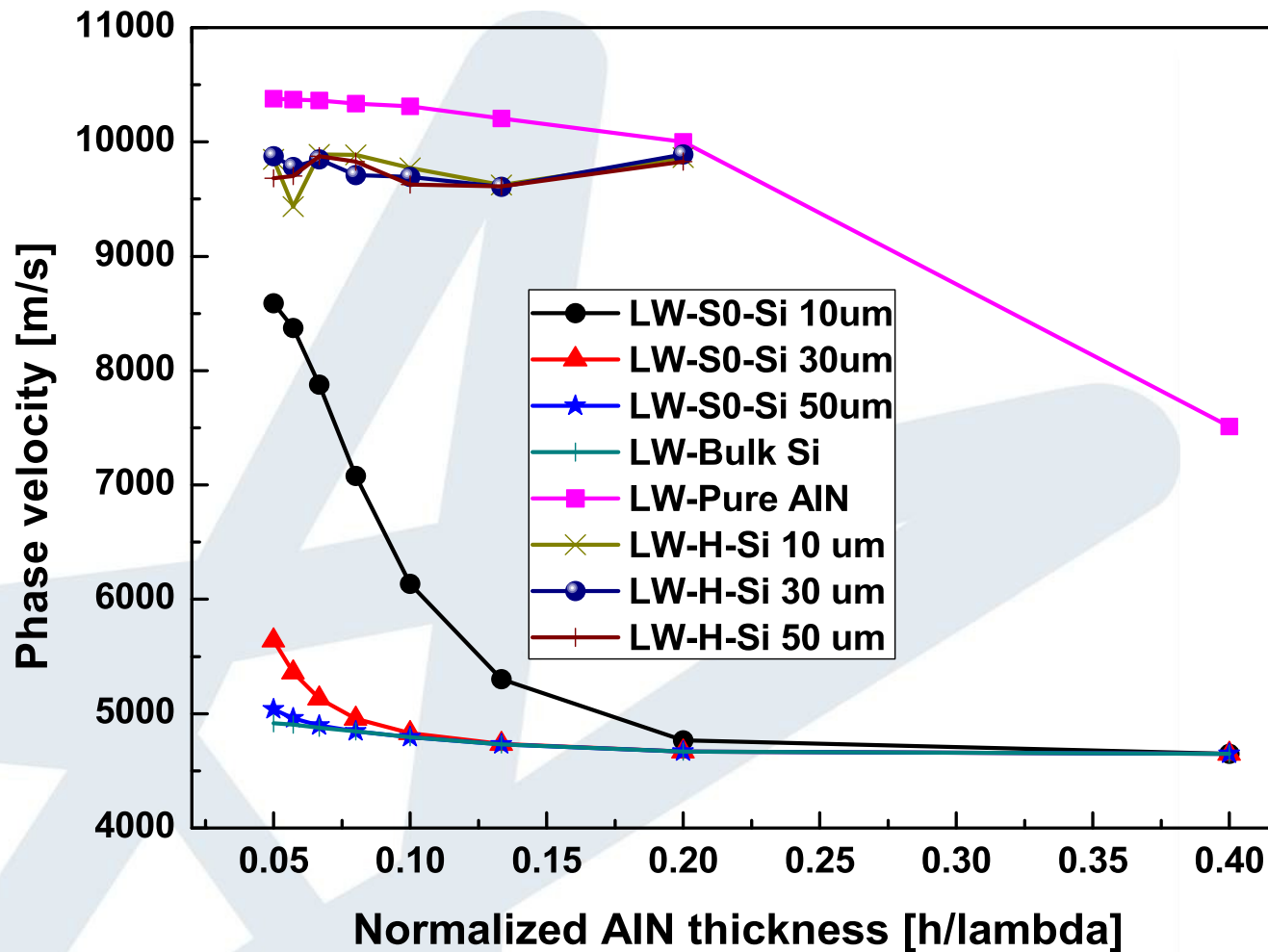


**511.078 MHz**

Lamb wave



# Simulation results



The simulated dispersion curves of LAMB waves

The phase velocity dispersive curve of the Lamb wave under different Si thickness (Bulk, 10  $\mu\text{m}$ , 30  $\mu\text{m}$  and 50  $\mu\text{m}$ ) are simulated. Compared with the phase velocity dispersion curves of Lamb wave in pure AlN/Al plate, higher order Lamb wave shows a non-dispersive behavior over a wide range.

# Stress investigation of metal thin film microbolometer

# Stress investigation of metal thin film microbolometer

Metal (Pt, Au, Ag, Ni, ...) and dielectric (SiO<sub>2</sub>, SiN, Al<sub>2</sub>O<sub>3</sub>, ...) thin films are used extensively in microelectromechanical system (MEMS) devices as structural layer. **Stress control** of these films is of particular importance to guarantee integrity and reliability of the MEMS devices. Stress-free of film stacks is required to achieve **membrane flatness**, which is very critical in some MEMS devices, especially microbolometer to ensure optimum light exposure and absorption.

Stress is developed throughout the film deposition process due to **lattice mismatch and thermal expansion coefficient** difference between deposited film and material underneath. The film stress can be minimized by tuning the process parameters but it is a very time consuming and challenging task.

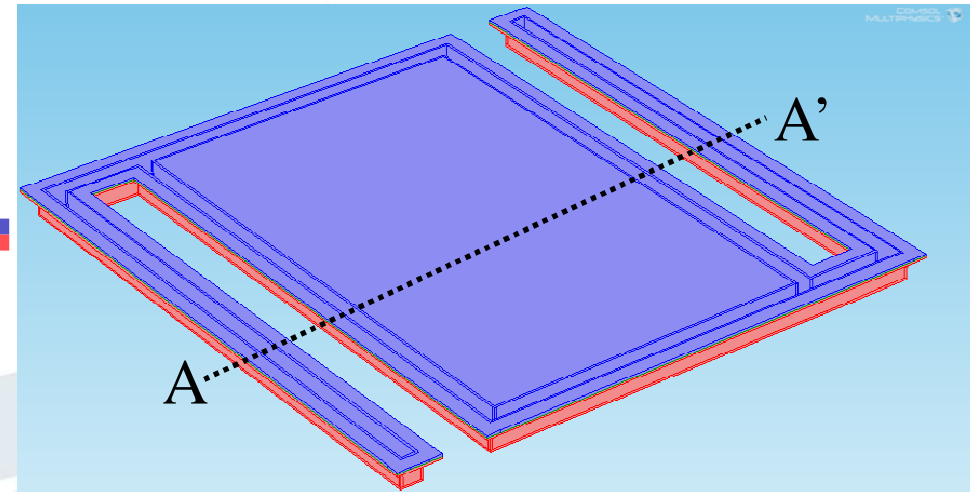
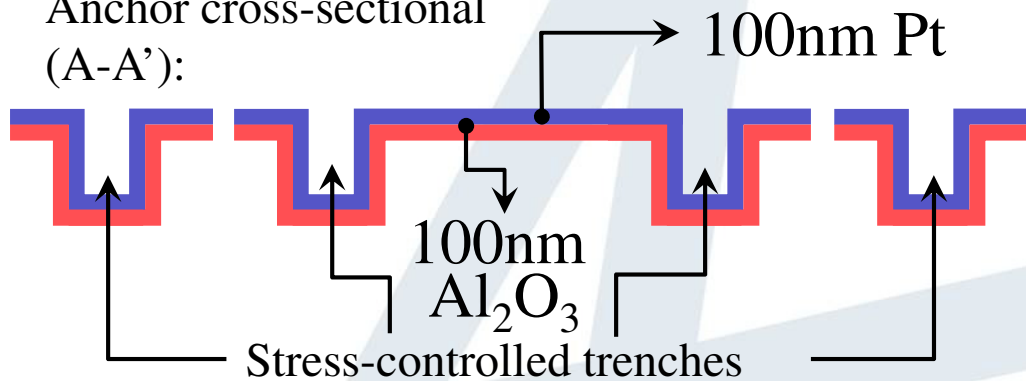
Simulations are thus employed to **design** the membrane structure that able to accommodate certain amount of film stress and still retain the membrane flatness. **Stress-controlled trenches** are added surrounding the free-standing membrane to improve the membrane flatness.

# Simulation approach

Physics employed: Solid Mechanics (solid)

## Materials

Anchor cross-sectional (A-A'):

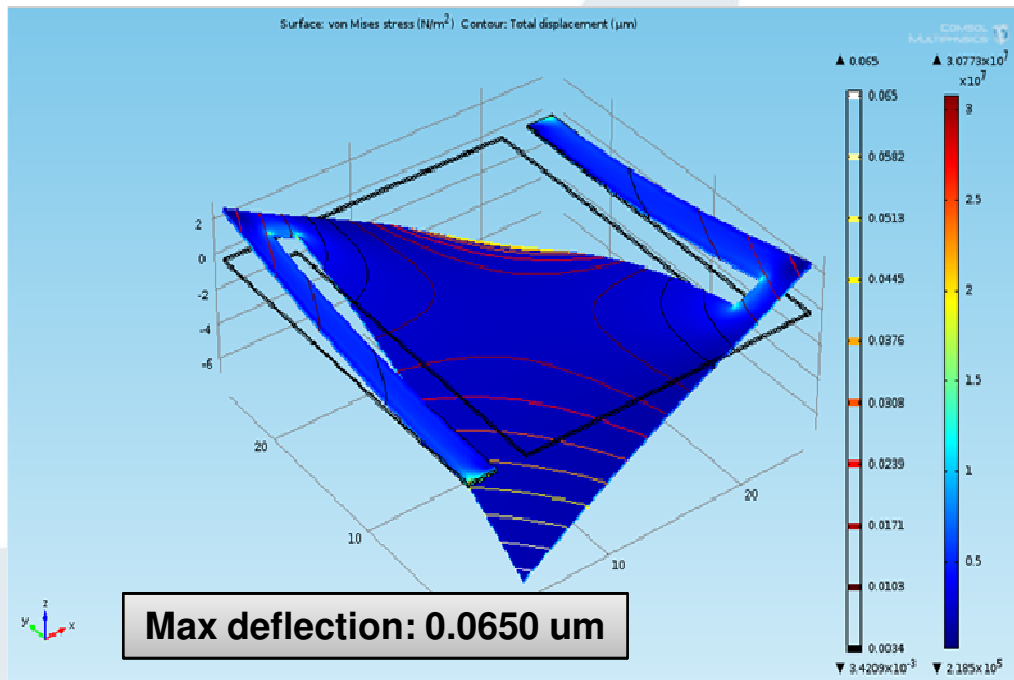


## Conditions Setting

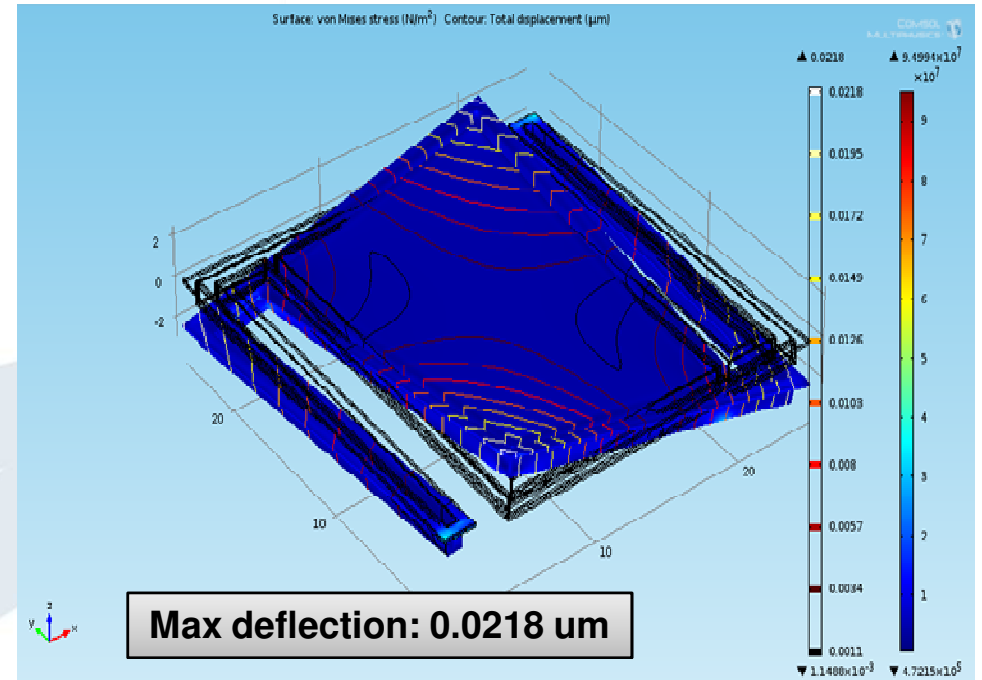
Domain	Linear Elastic Material	Initial Stress and Strain ( $\text{Al}_2\text{O}_3$ ) Initial Stress and Strain (Pt)	$S_o \text{ (N/m}^2\text{)} = \begin{bmatrix} 10e6 & 10e6 & 0 \\ 10e6 & 10e6 & 0 \\ 0 & 0 & 0 \end{bmatrix} \text{ (N/m}^2\text{)}$ $\epsilon_o (1) = \text{Default}$
Domain	Initial Values	Default	All domain
Boundary	Free	Default	All except "Fixed Constraint"
Boundary	Fixed Constraint		End of the two anchors

# Simulation Results

## Simulation without trenches



## Simulation with trenches



*By adding the stress-controlled trench at the periphery of the membrane, deflection reduced from 0.065 μm to 0.0218 μm.*

# Thermal behavior of acoustic wave microbolometer

# Thermal behavior of acoustic wave microbolometer

Figure-of-merit (FOM) of a bolometer is determined by the device sensitivity and speed. Time dependent study of heat transfer physics in the simulation can be employed to obtain the **thermal time constant (speed)** and amount of **temperature rise (sensitivity)** of the bolometer.

The important parameters to describe a bolometer thermal behavior are heat capacity and thermal conductance. Since the **dimension of all the materials** used in the bolometer govern these two important parameters, device structure design is very critical.

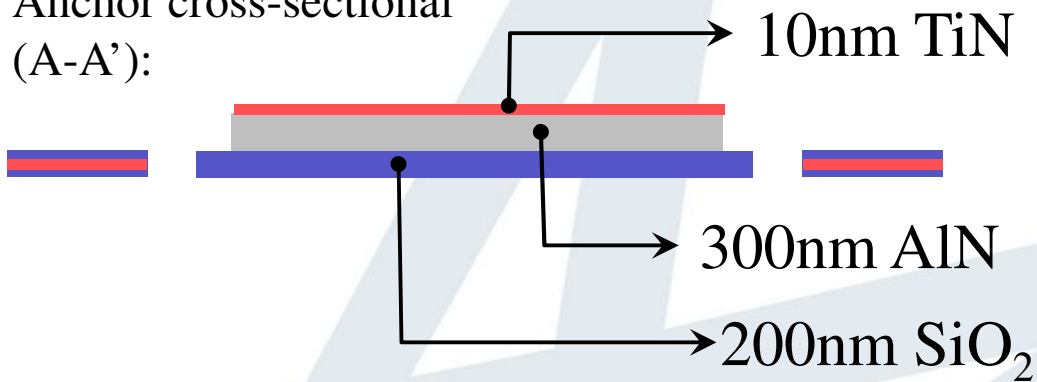
Depending on each particular application, bolometer can be designed with high speed or high resolution by optimizing the device structure design. However, **trade-off** is always needed **between speed and resolution**. Thus, the time dependent heat transfer is very useful to estimate the bolometer over performance.

# Simulation approach

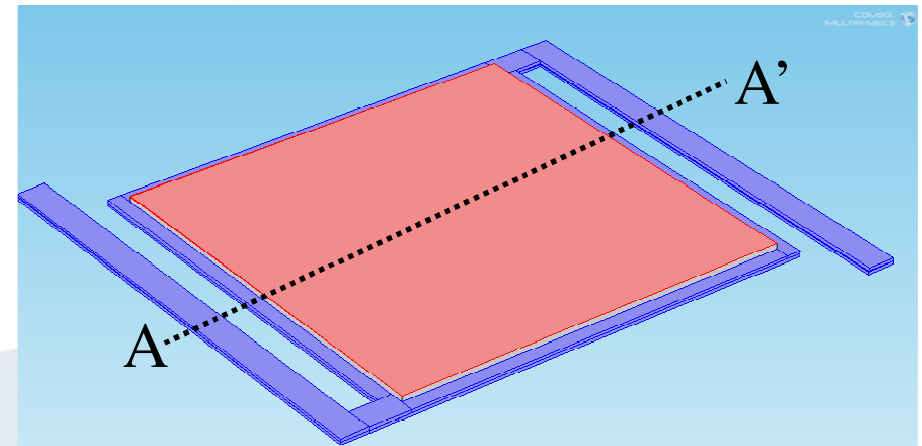
Physics employed: Heat Transfer (ht)

## Materials

Anchor cross-sectional  
(A-A'):



3D model of AW Microbolometer



## Conditions Setting

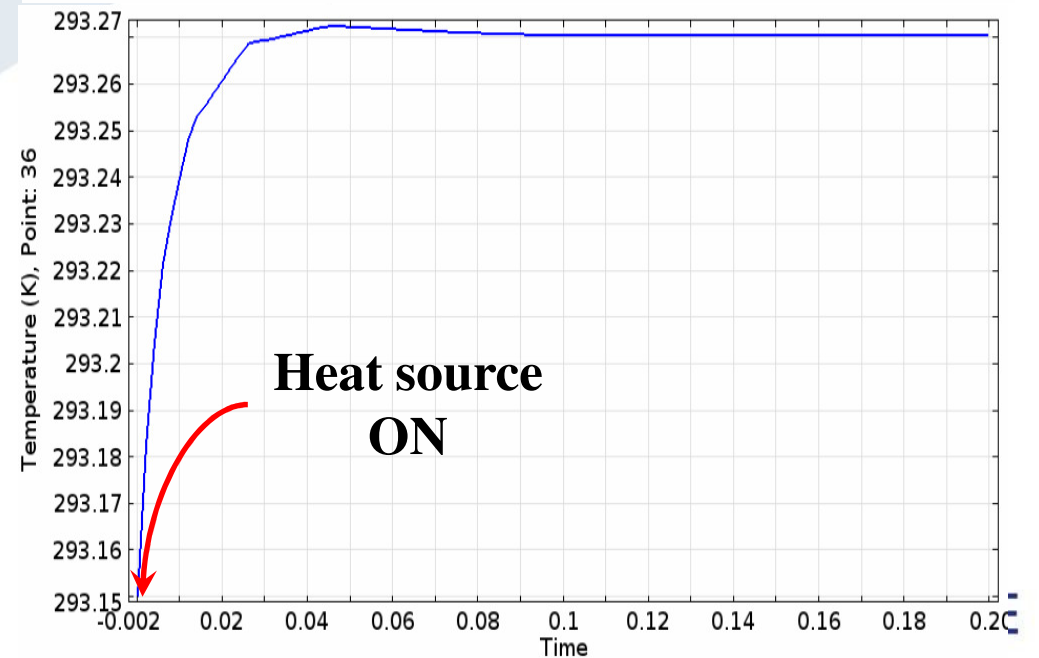
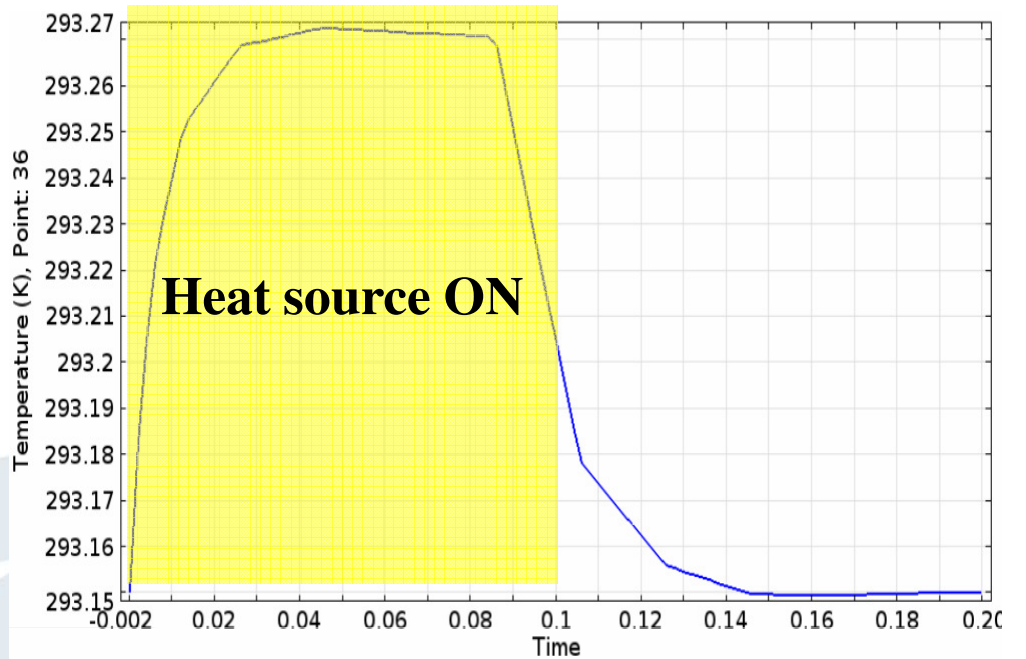
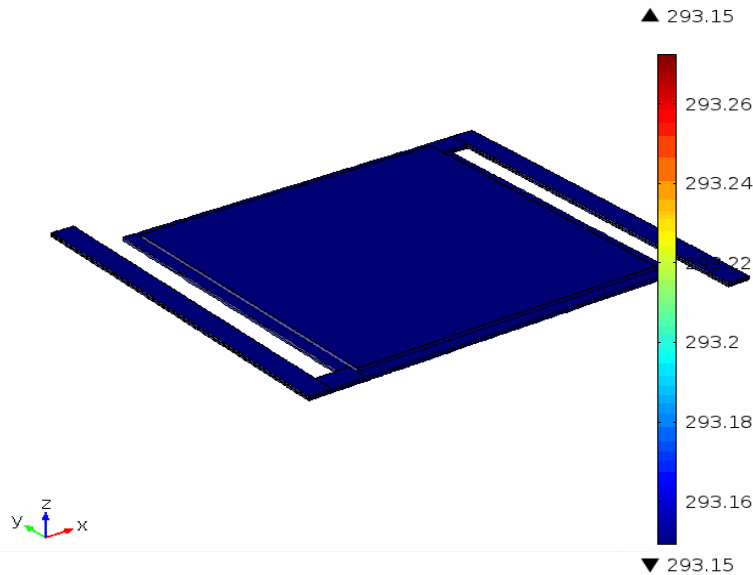
Domain	Heat Transfer in Solids	Default	All domain
Domain	Initial Values	Default	All domain
Boundary	Thermal Insulation	Default	All except "Temperature" and "Boundary Heat Source"
Boundary	Temperature	T = room temperature	End of the two anchors
Boundary	Boundary Heat Source	General source $Q_b = 20 \cdot 0.5 \cdot (\text{sign}(t) - \text{sign}(t - 0.1))$ W/m <sup>2</sup>	Top surface of TiN on top of AlN



# Simulation Results

## Thermal profile

Time=0 Surface: Temperature (K)



*Temperature profile and the change of temperature with time.*

*The maximum temperature rise within the free-standing membrane was obtained directly from the simulation.*

*Thermal time constant can be extracted by fitting the curve below with exponential function.*

# Fluid-structure interaction (FSI) model for piezoelectric based energy harvest

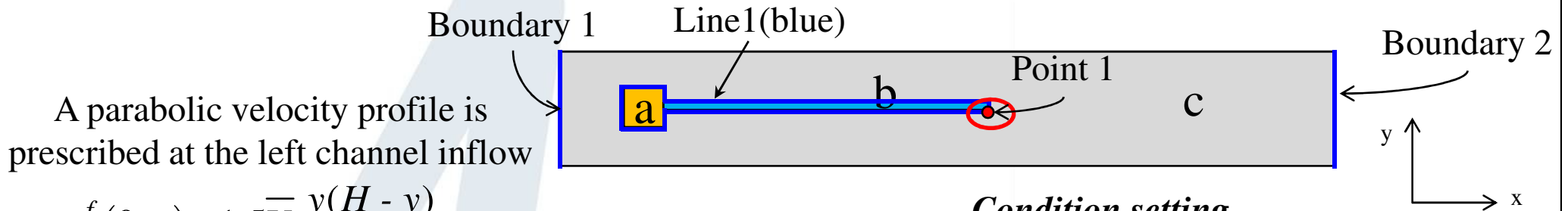
# Fluid-structure interaction (FSI) model for piezoelectric based energy harvest

Plenty of **energy** can be taken from surrounding **fluid sources**. A classical flow pattern is the von **Kármán vortex street** that can form as fluid flows past an object. These vortices may induce vibrations in the object. This vortex shedding phenomenon is implemented by IME in the development of a **MEMS micro-belt (AIN)** based **energy harvester**.

Thus, have a good **understanding on the fluid-structure interaction** behavior is critical to guide the MEMS device design. In this simulation, we look into the fluid velocity, beam stress, force versus time and beam tip displacement in x and y directions.

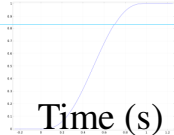
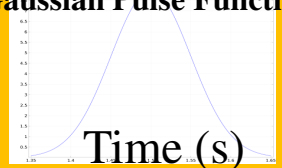
# Simulation approach

Physics employed: Fluid Flow>Fluid-Structure Interaction (fsi)

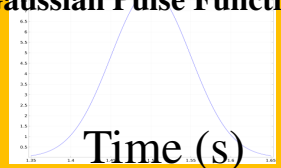


$$v^f(0, y) = 1.5\bar{U} \frac{y(H - y)}{(H/2)^2}$$

## Definitions

Function (step 1) 	Location: 0.5 Smoothing: size of transition zone (1)
Function (Gaussian Pulse 1) 	Location: 1.5 (s) Standard deviation: 5e-2(s)
Integration	Line1(blue) All Boundary
Global Variable Probe	Lift: -intop1(fsi.T_stressx) Drag: -intop1(fsi.T_stressy)

## Condition setting

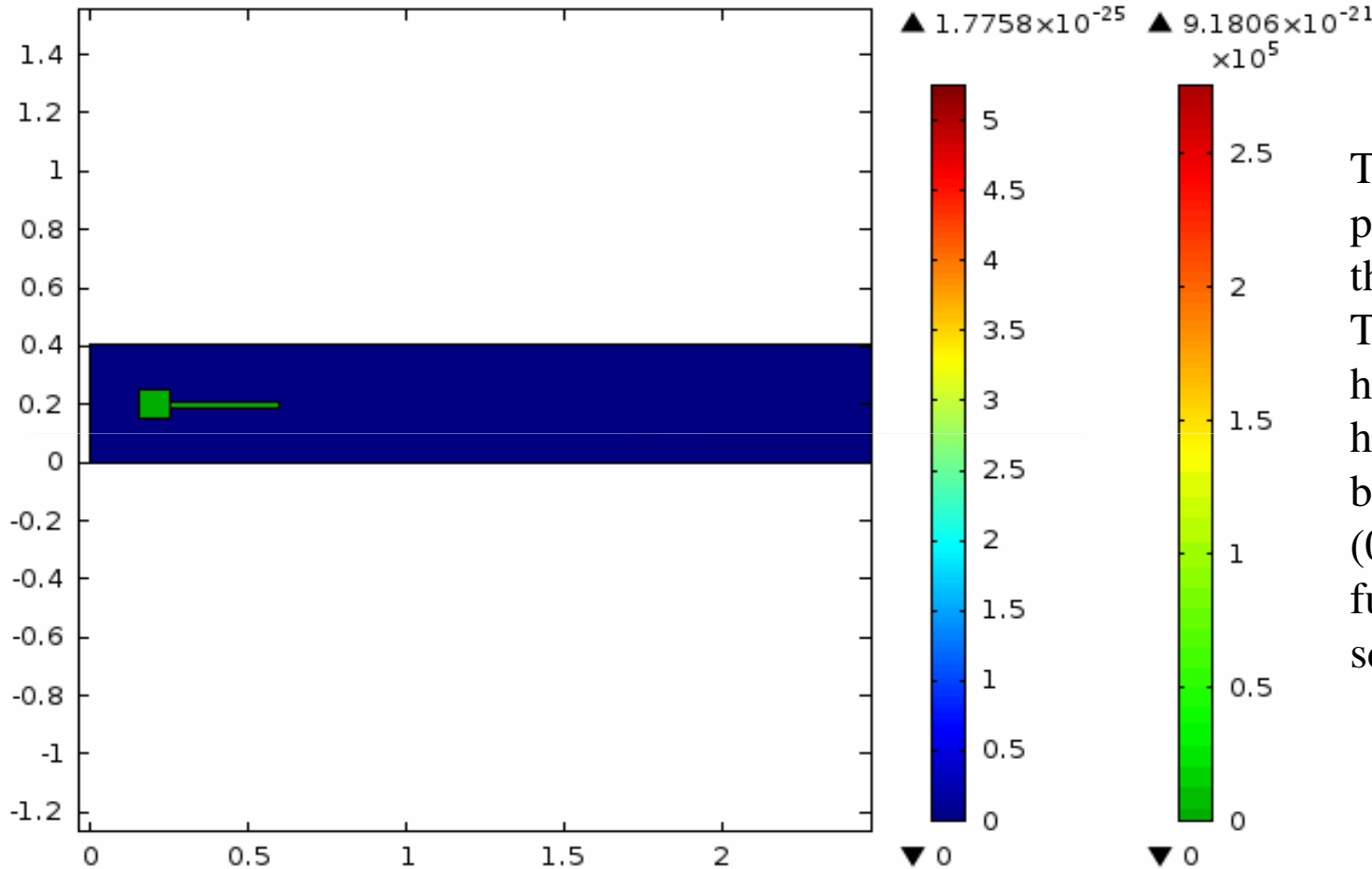
Fluid-Structure Interaction	Reference Point for Moment Computation>Discretization > Discretization of fluids choose <b>P2+P1</b> <b>P2: 2<sup>nd</sup>-order Lagrange elements model the velocity components</b> <b>P1: linear elements model the pressure</b>				
Fixed Constraint 1	Block <b>a</b> fixed				
Point Load 1	Force: <b>point 1</b> <table border="1" data-bbox="1294 1021 1568 1141"> <tr> <td>0</td> <td>x</td> </tr> <tr> <td>gp1(t)</td> <td>y</td> </tr> </table> 	0	x	gp1(t)	y
0	x				
gp1(t)	y				
Inlet 1	Laminar Flow>Inlet select <b>Boundary1</b> $U0: 1.5*2[m/s]*y*(0.41[m]-y)/(0.41[m]/2)^2*step1(t)$				
Outlet 1	Laminar Flow>Inlet select <b>Boundary2</b> P: 0				

**Mesh:** Element size (Fine)

**Studies:** Time Dependent; Type 0 range (5, 5e-3, 6)

# Simulation Results

Time=0 Surface: von Mises stress (N/m<sup>2</sup>) Surface: Velocity magnitude (m/s)  
Arrow Surface: Velocity field (Spatial)



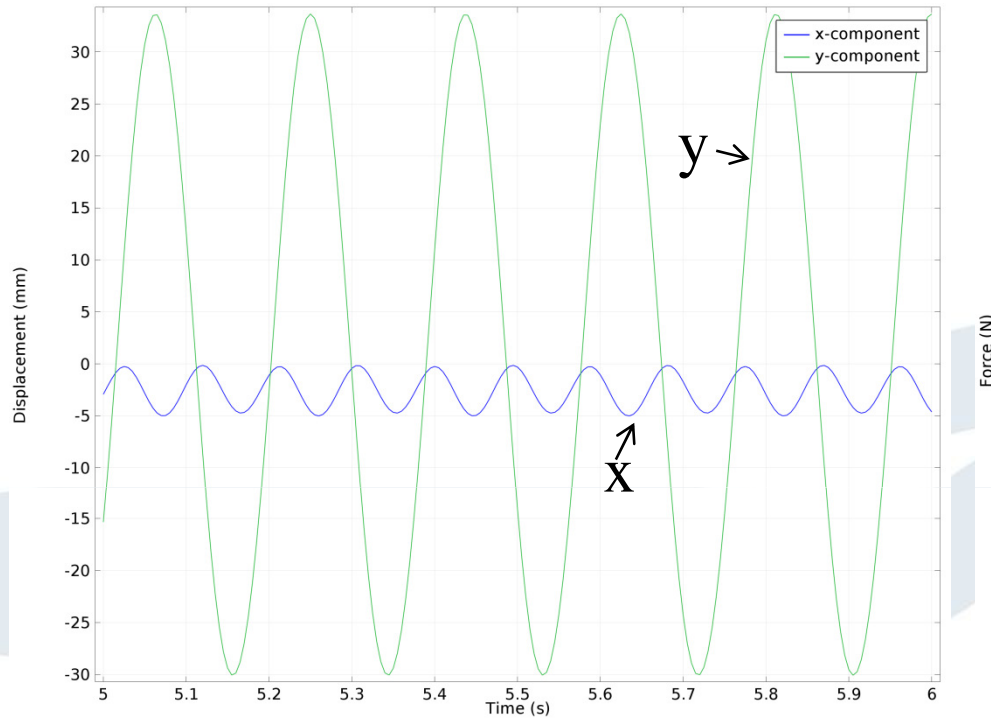
Channel length  $L$ : 2.5 m,  
Channel height  $H$ : 0.41 m

The bluff body square is positioned at  $C=(0.2, 0.2)$  and the side length is 0.1 m.

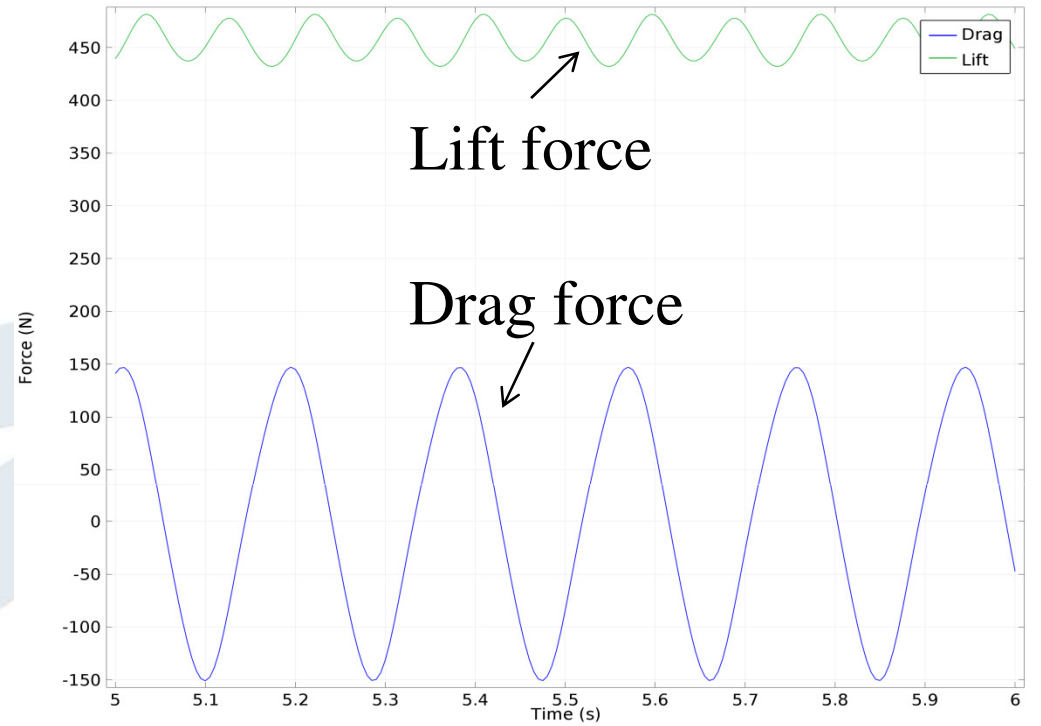
The elastic structure beam has length  $l=0.35$  m and height  $h=0.02$  m, the right bottom corner is positioned at  $(0.6, 0.19)$ , and the left end is fully attached to the fixed square.

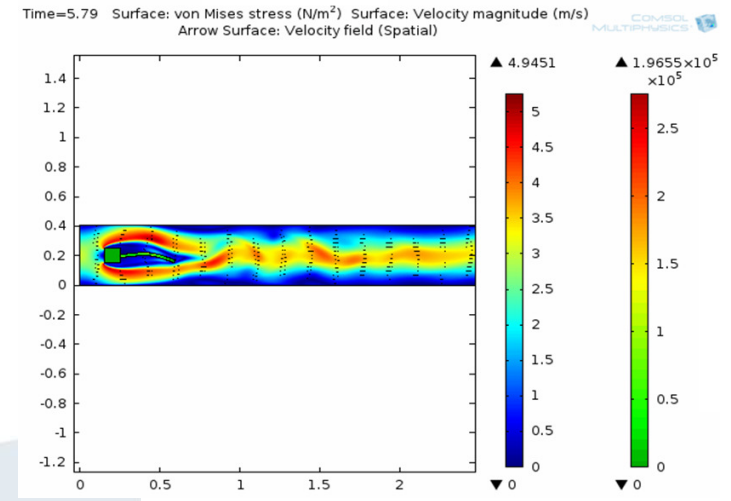
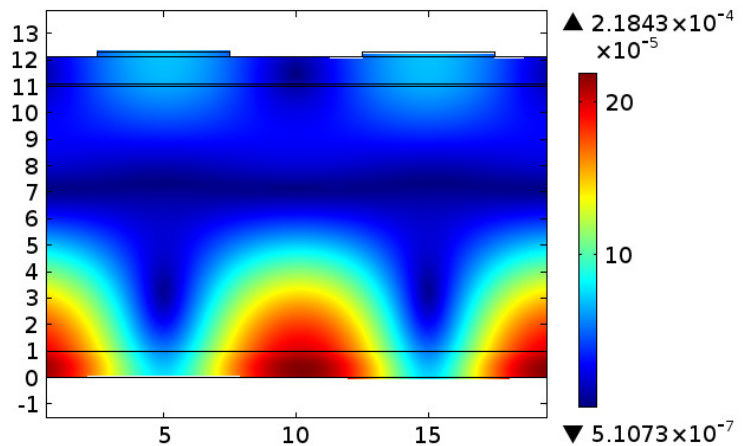
# Simulation Results

## Displacement of point 1



## Lift and drag force of point 1





**Thank you for your attention!**  
**Questions?**

